

EXPERTISE AT UGENT

THIN FILMS

OUR TOOLBOX

In situ characterization during annealing, ALD and plasma treatment

- ▶ In situ XRD
- ▶ In situ optical emission spectroscopy
- ▶ In situ laser light scattering
- ▶ In situ Ellipsometer
- ▶ In situ 4-point measurements
- ▶ In situ wafer curvature measurements
- ▶ In situ mass spectroscopy and FTIR



Post-application analysis

- ▶ Thermal analysis
- ▶ Microstructural & crystallographic analysis
- ▶ Texture analysis
- ▶ Mapping Equipment
- ▶ Magnetic and electric properties



Pre-application analysis

- ▶ Solution characterization
- ▶ Powder and particle processing
- ▶ Powder and particle characterization

